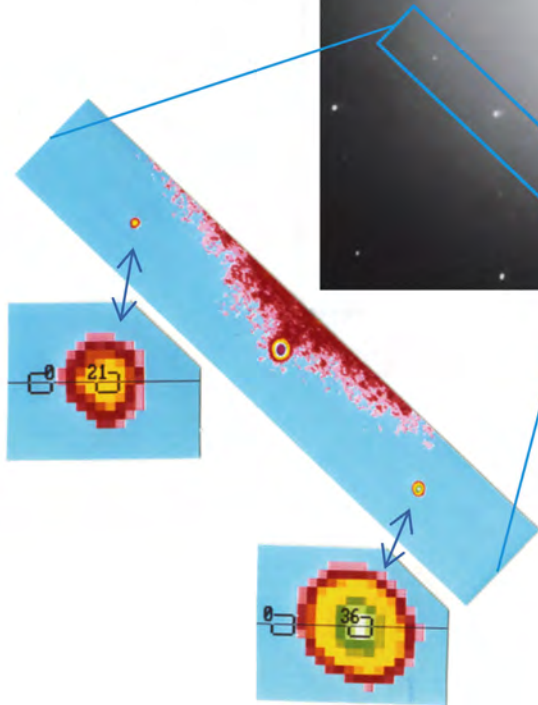
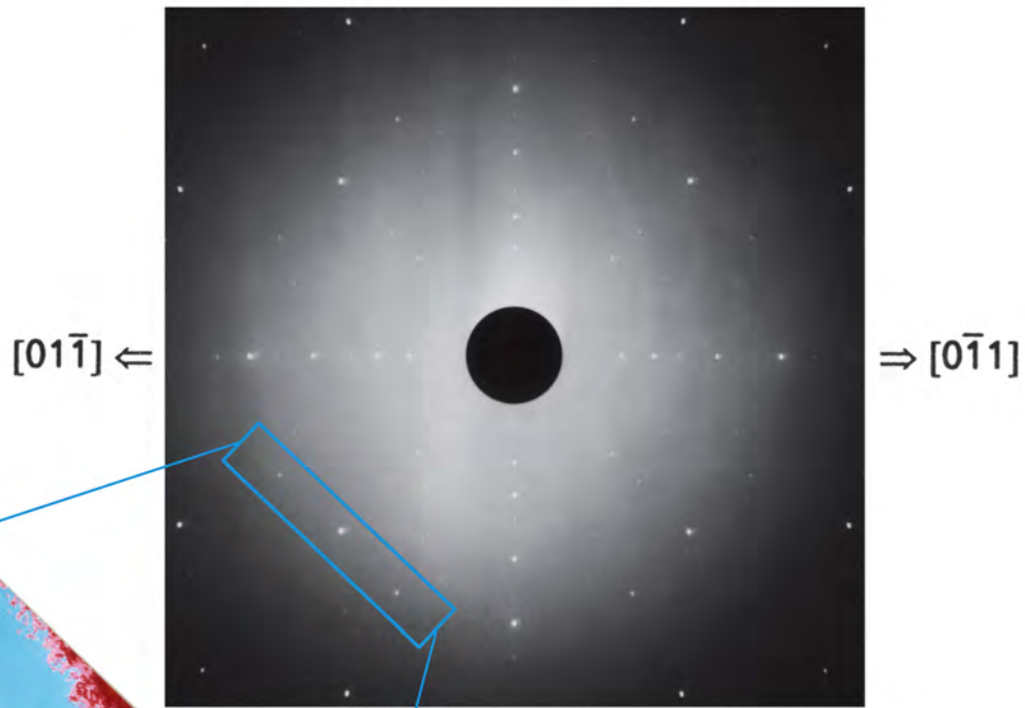
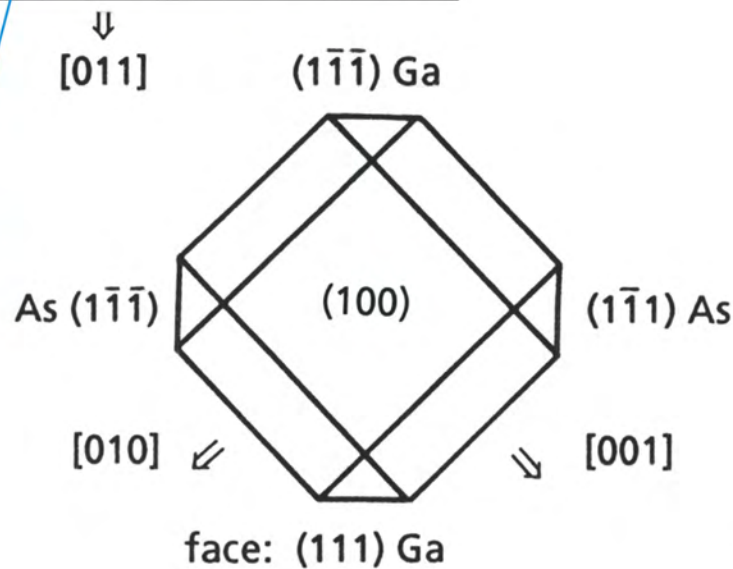


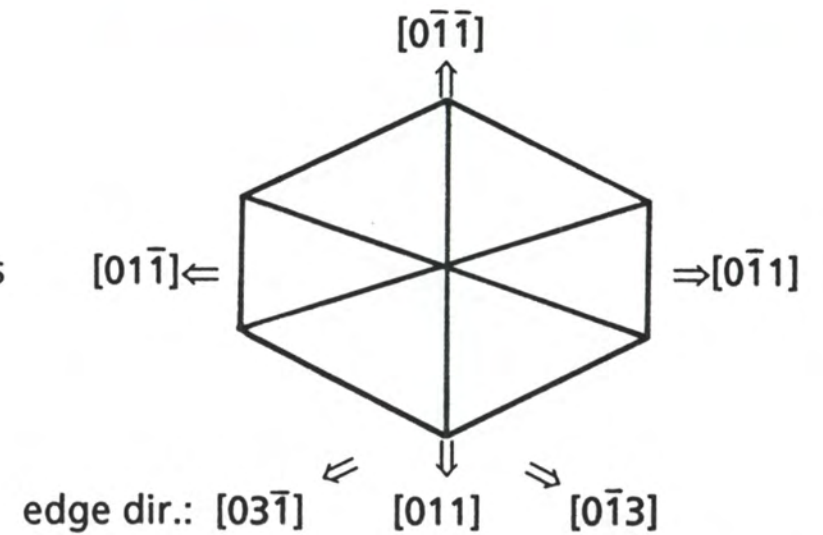
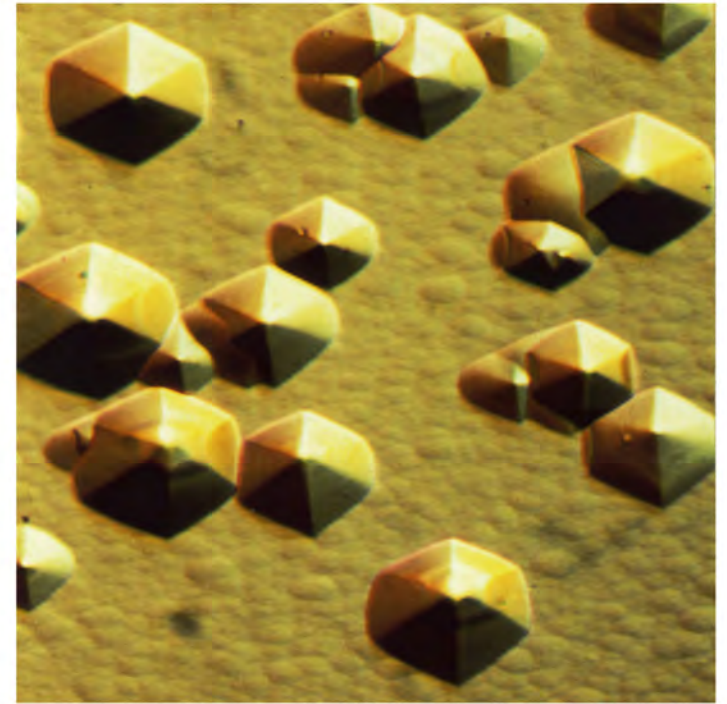
Laue back reflection pattern



weak: reflection $93\bar{1}$
 strong: reflection 931
 ($\lambda = 1.12 \text{ \AA}$)

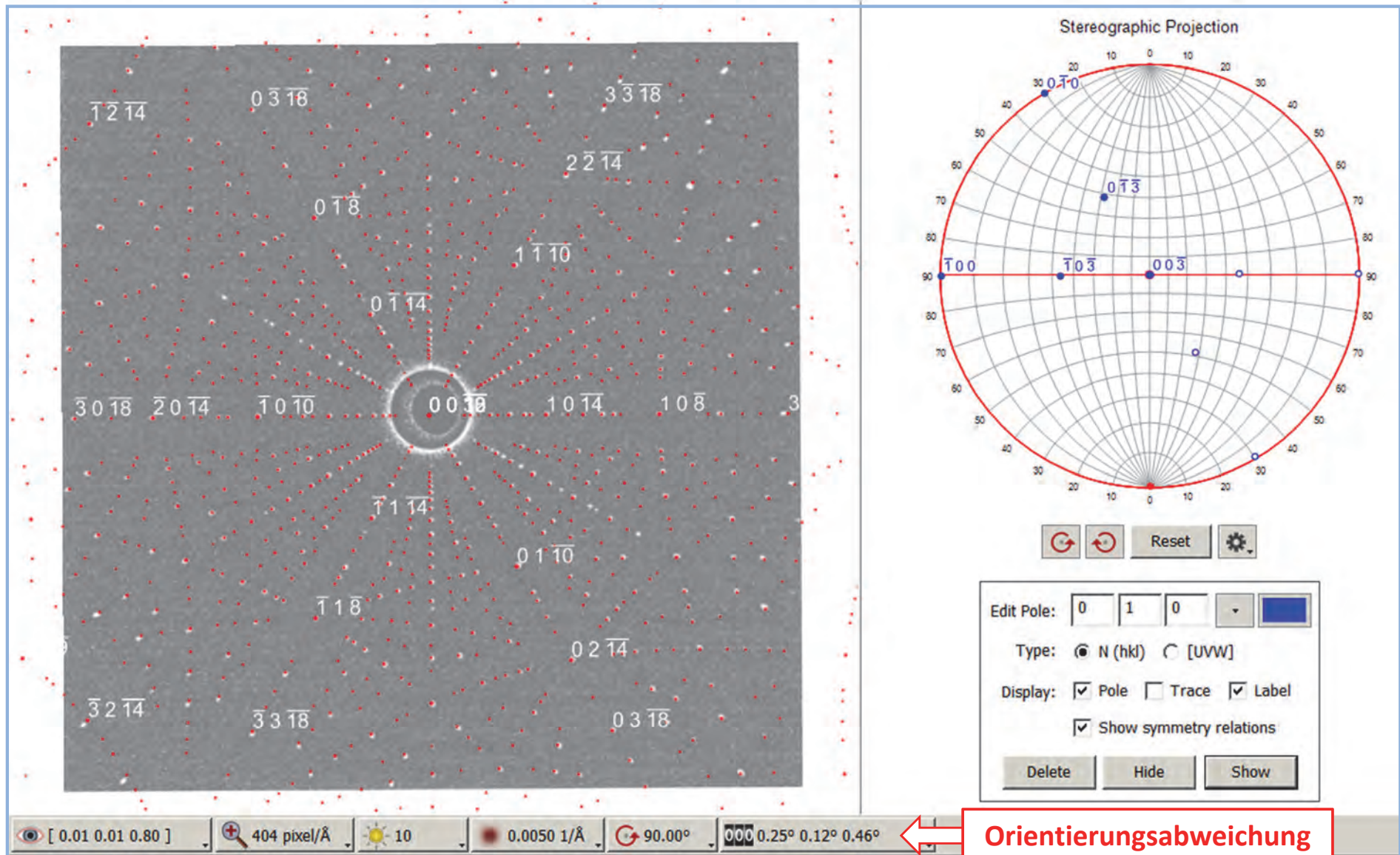


Optical micrograph (Nomarski-IC)

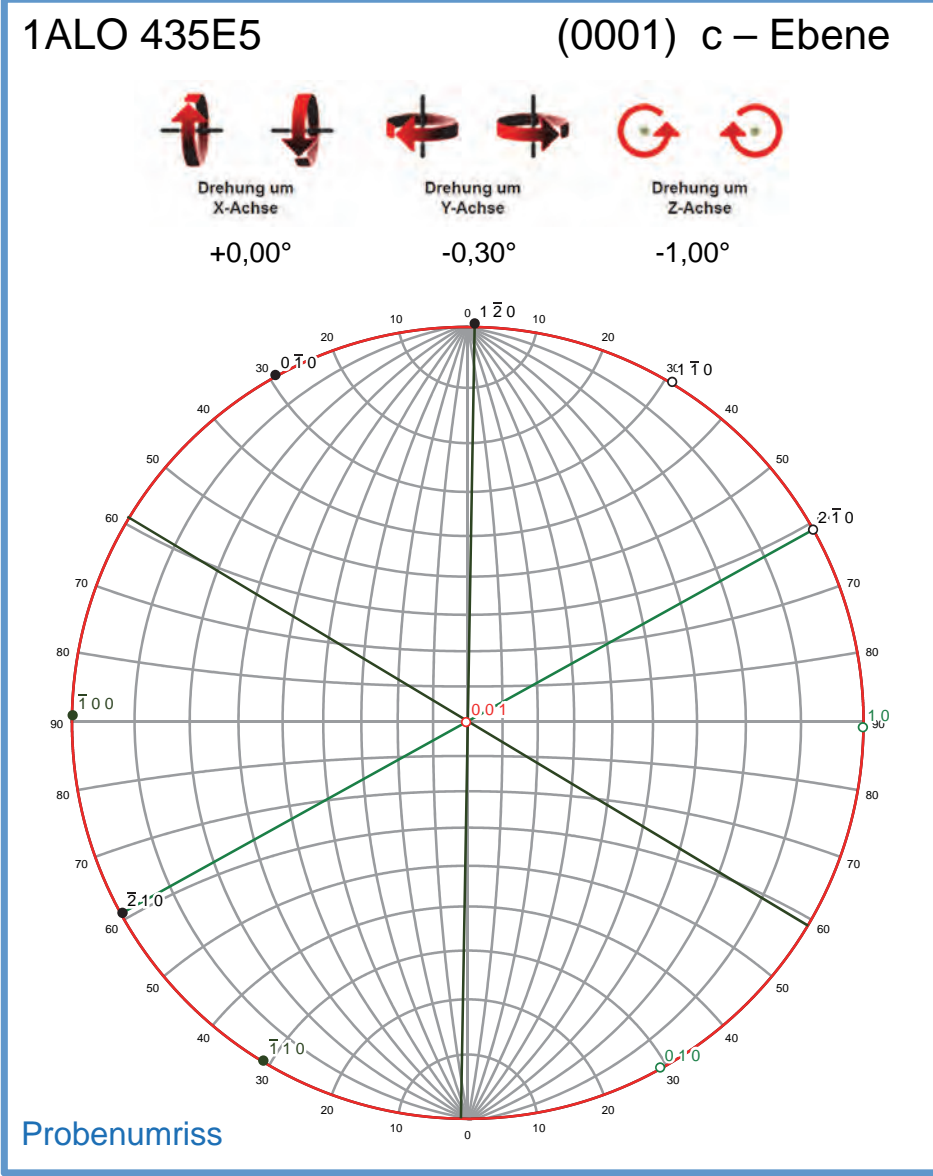
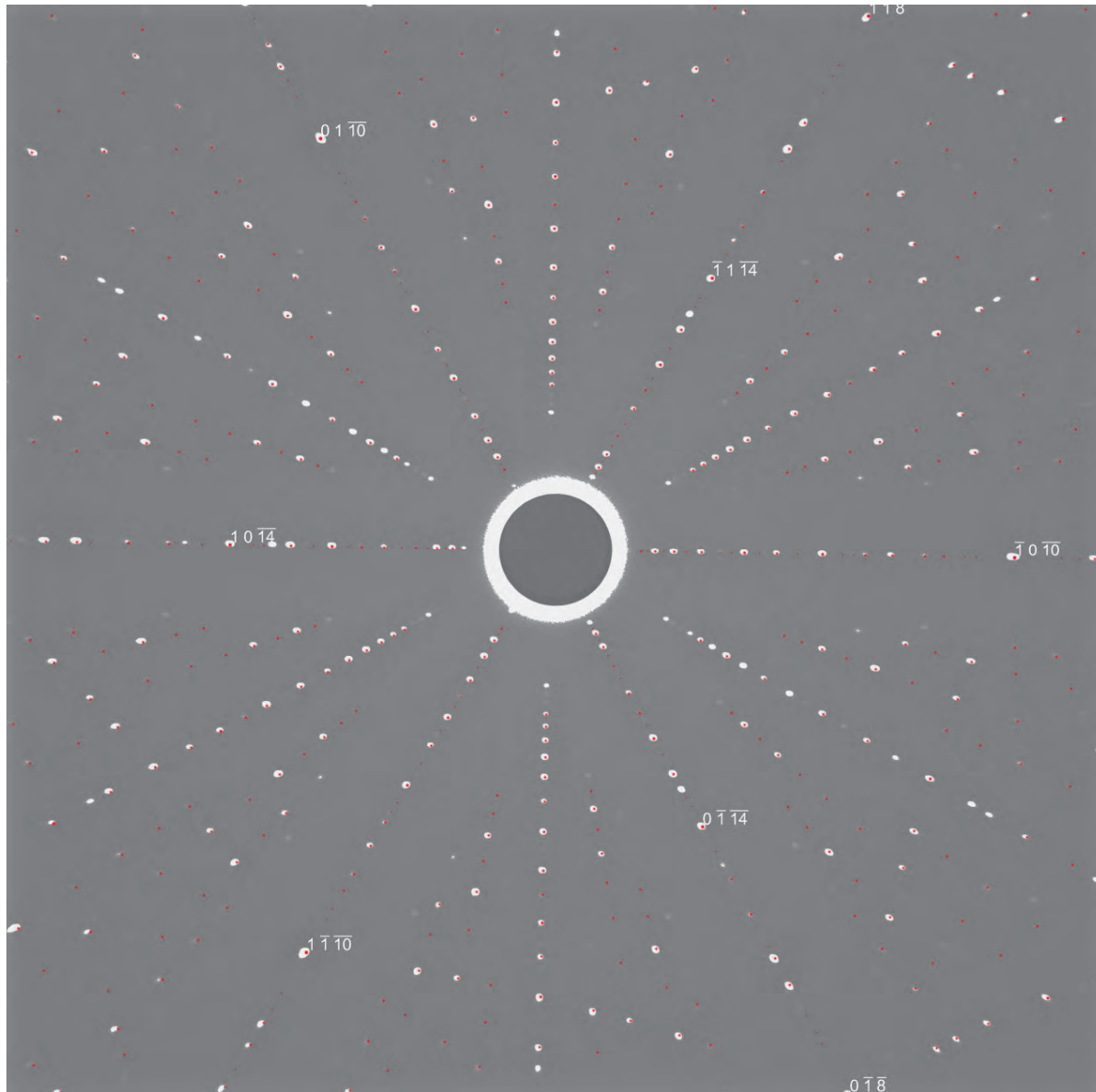


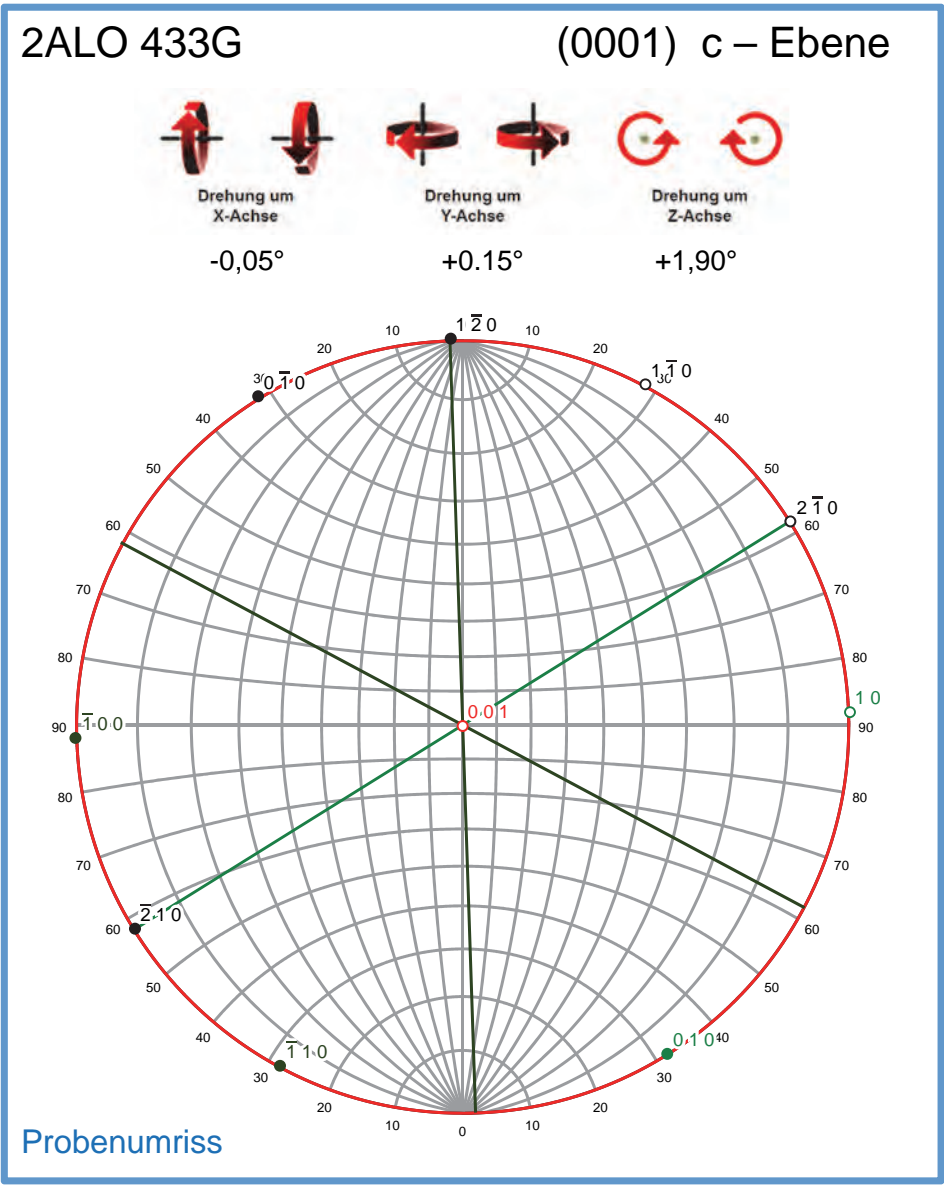
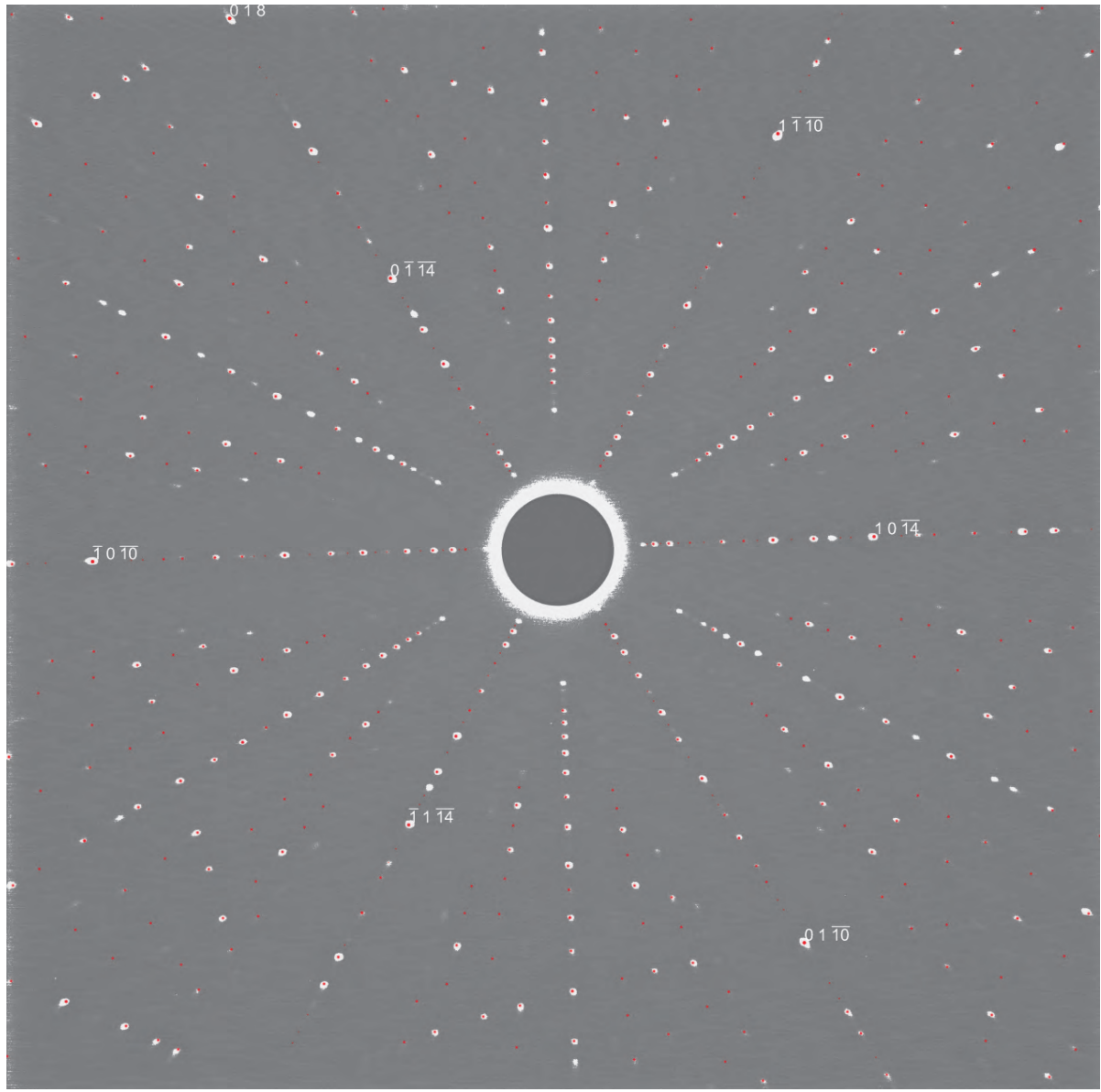
Laue-Rückstrahl-Diagramm von Saphir

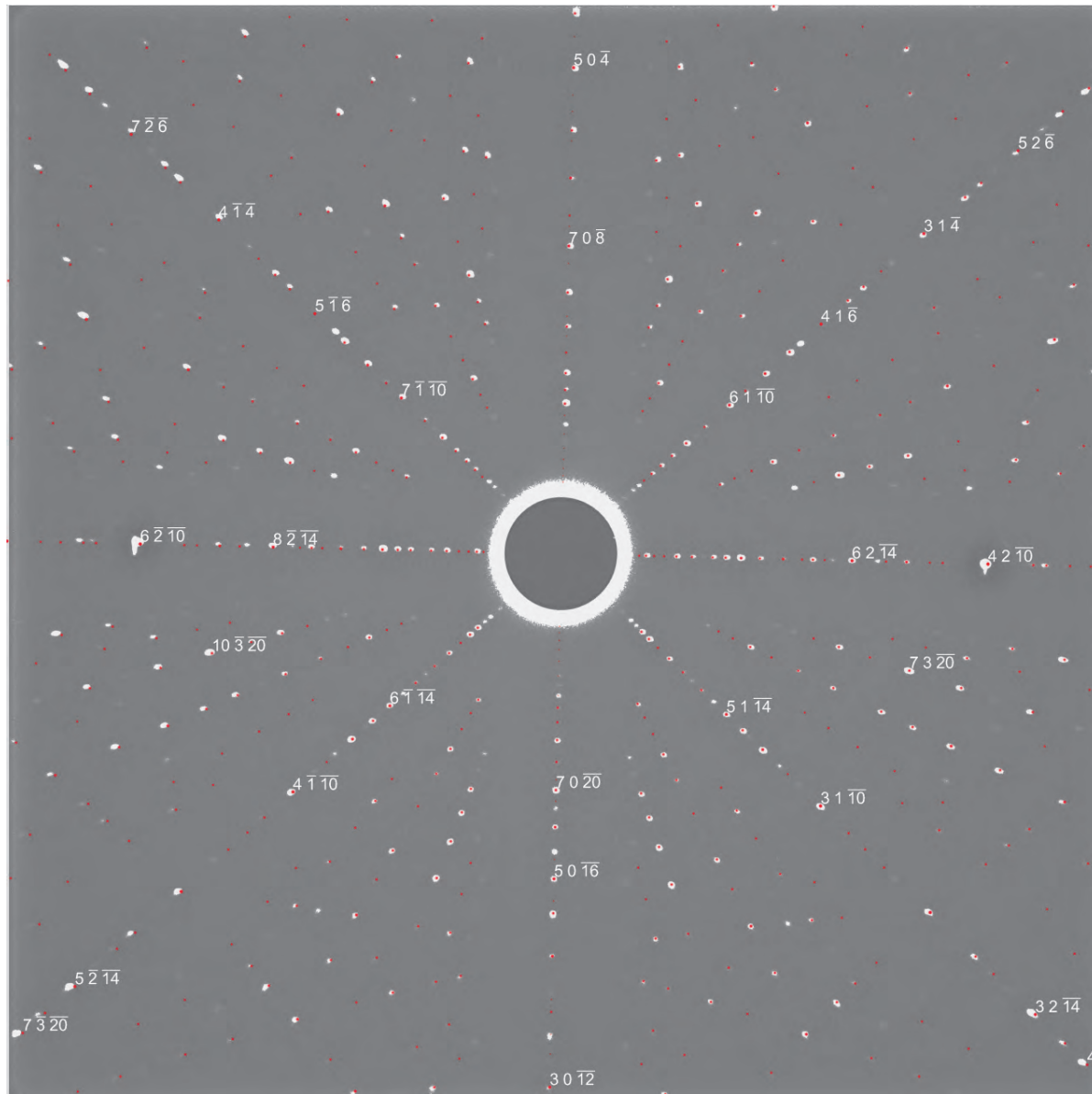
Einstrahlrichtung des Röntgenstrahls: senkrecht zur (0001) Fläche



Messung: Wolfram-Röhre, U = 45 kV, Kristall-Film-Abstand: 40 mm
Modellierung: SingleCrystal™ for Windows, CrystalMaker Software Ltd







1ALO 535E5

$(10\bar{1}2)$



Drehung um
X-Achse

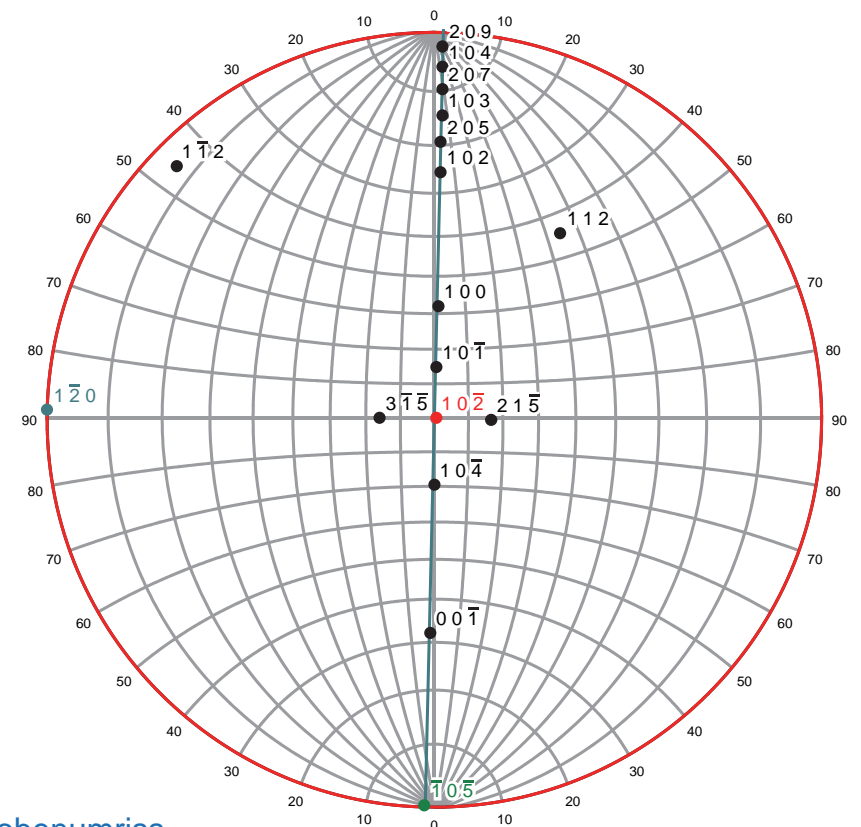
Drehung um
Y-Achse

Drehung um
Z-Achse

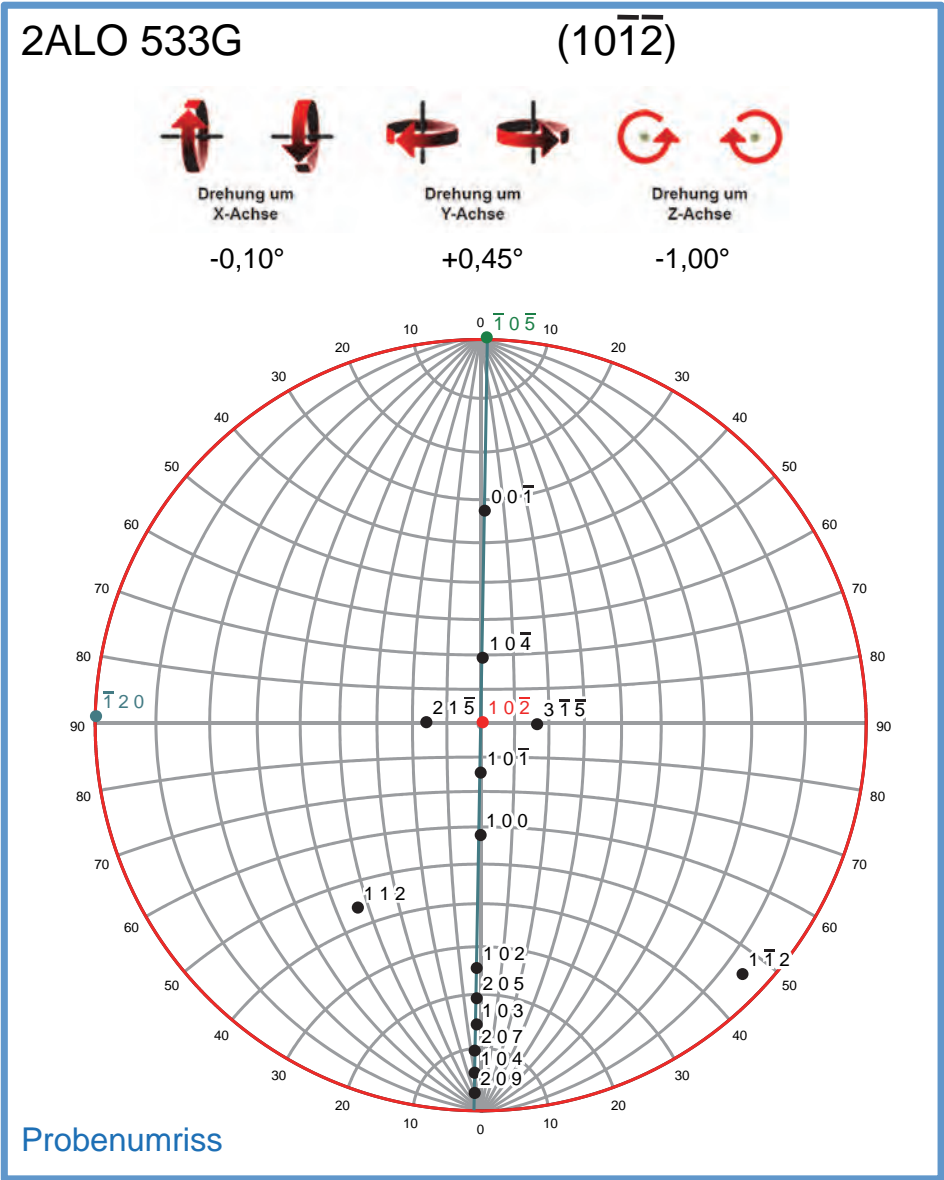
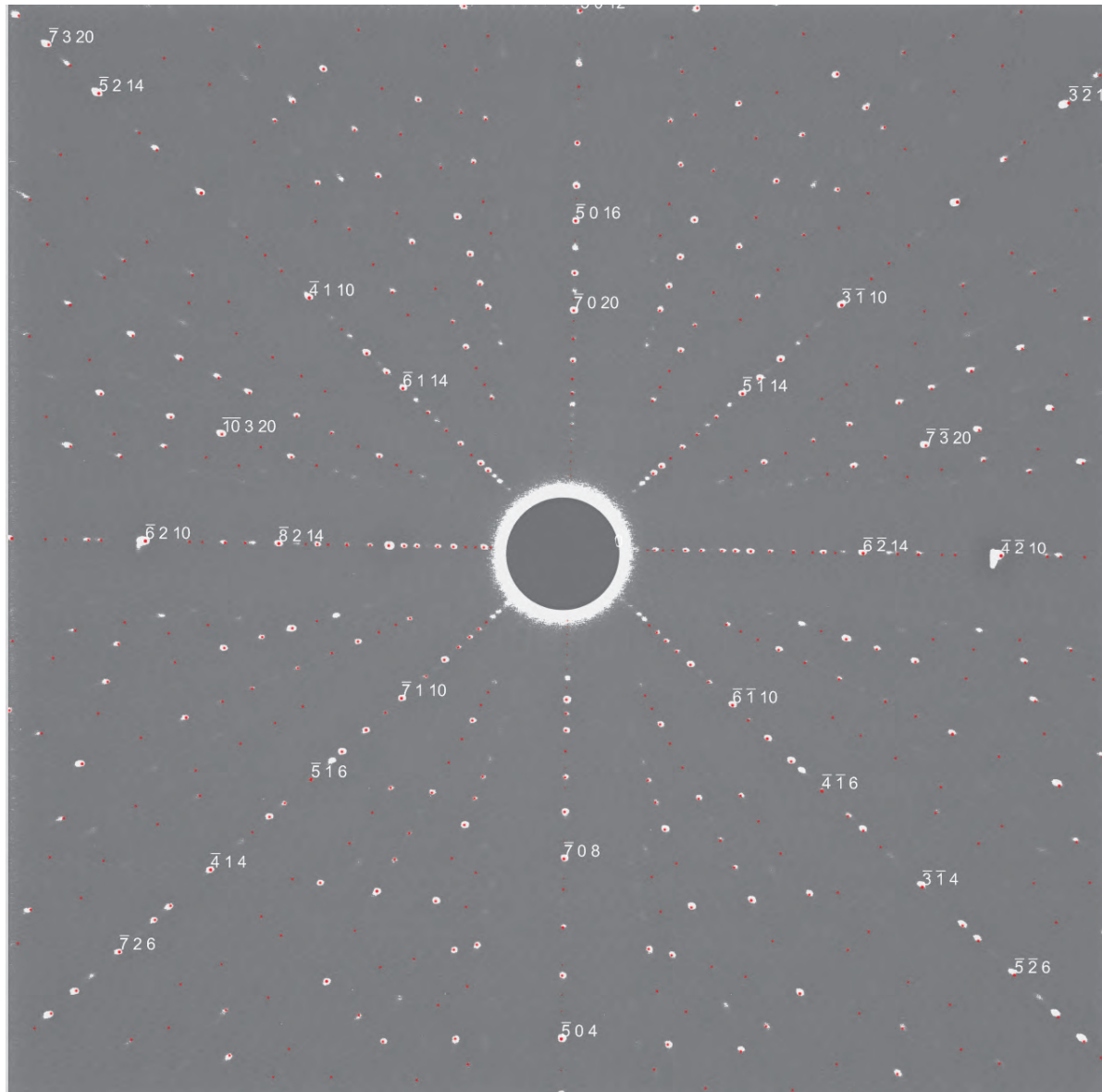
+0,10°

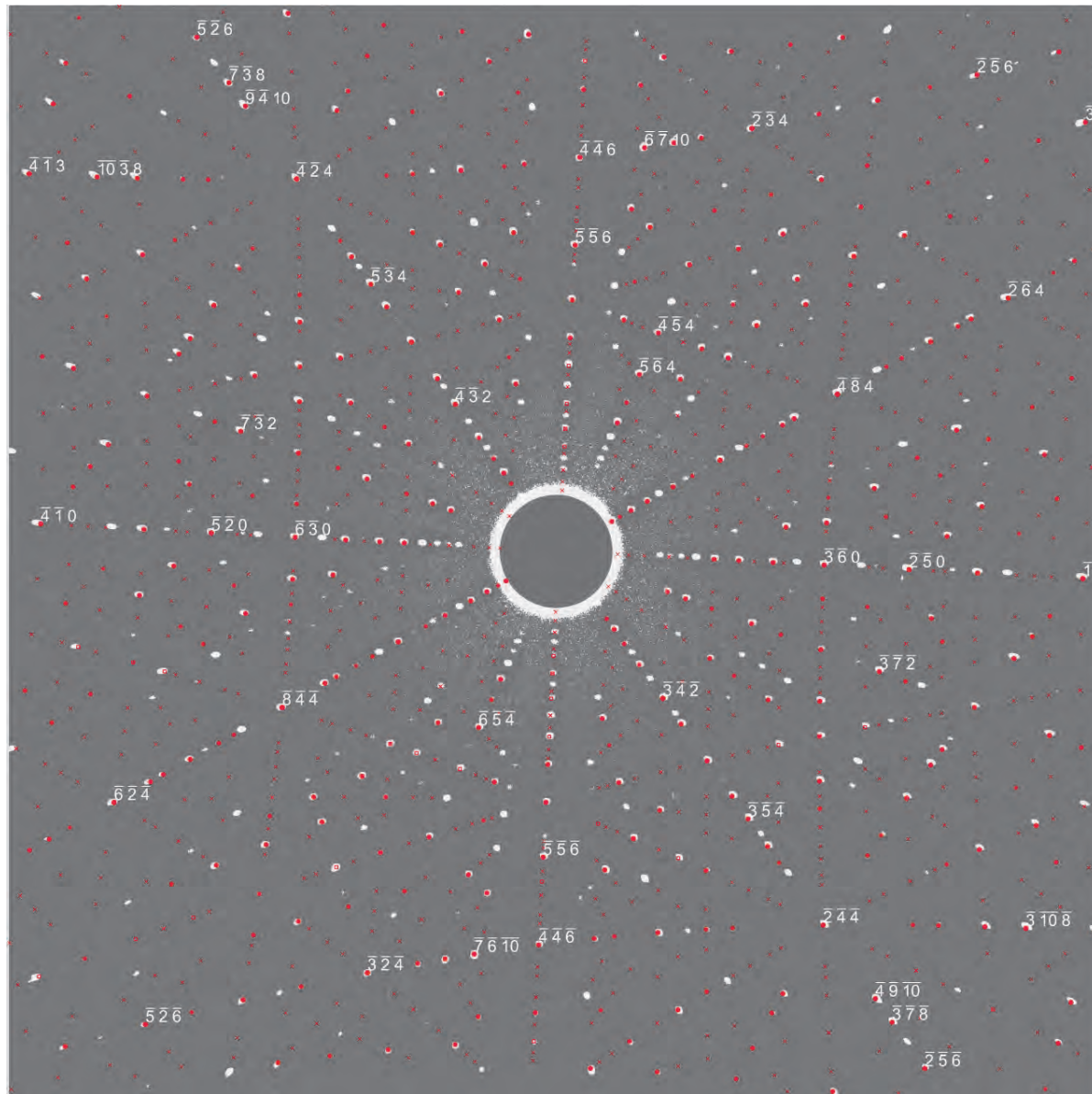
+0,30°

-1,35°



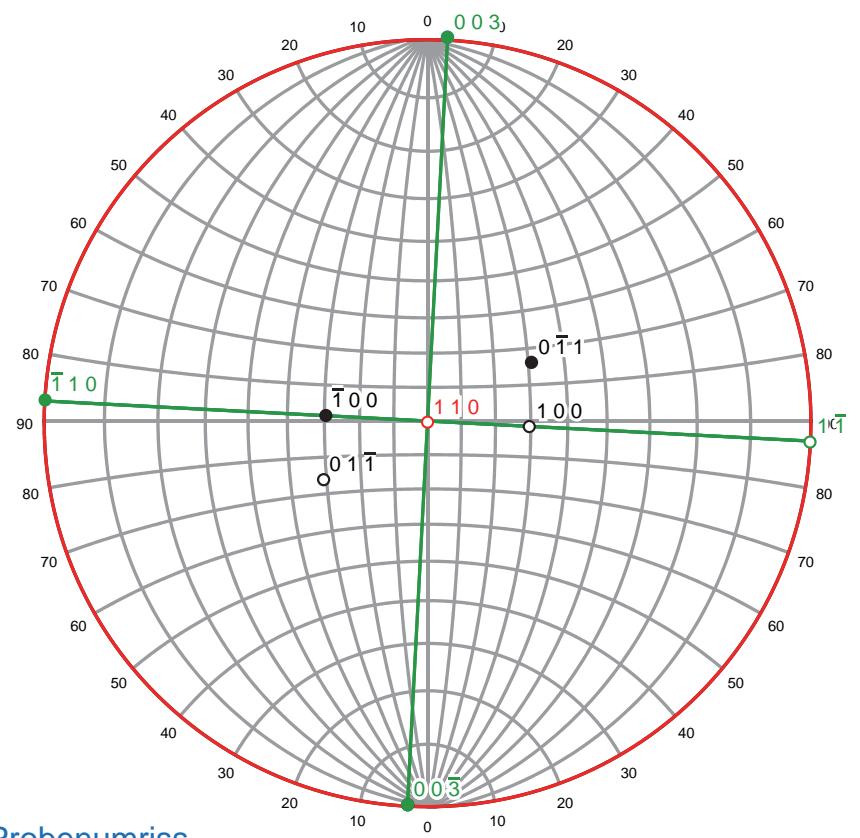
Probenumriss



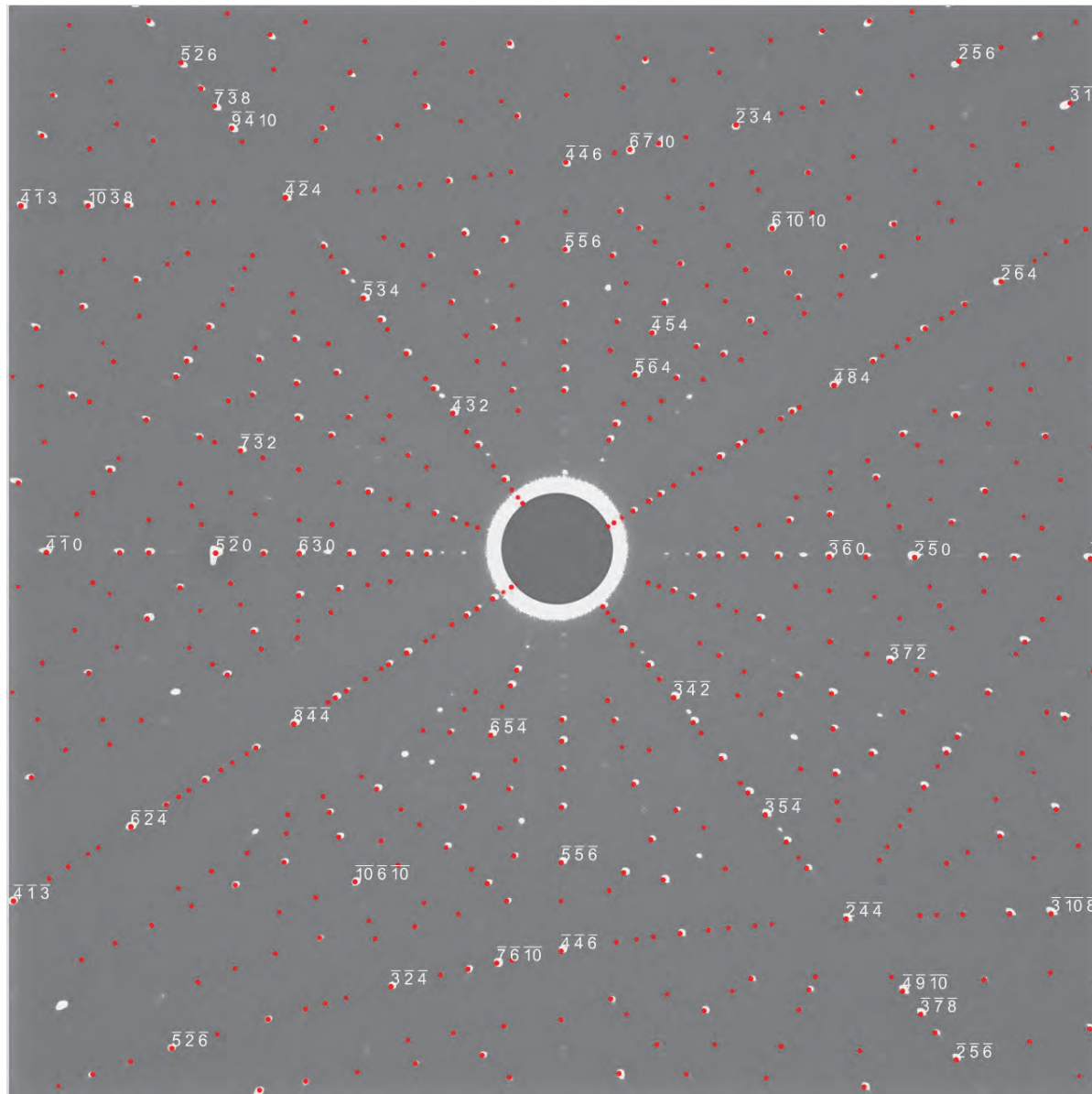


1AL0 635E5

$(11\bar{2}0)$ a - Ebene



Probenumriss



2ALO 633G

(11 $\bar{2}0$) a - Ebene



Drehung um X-Achse

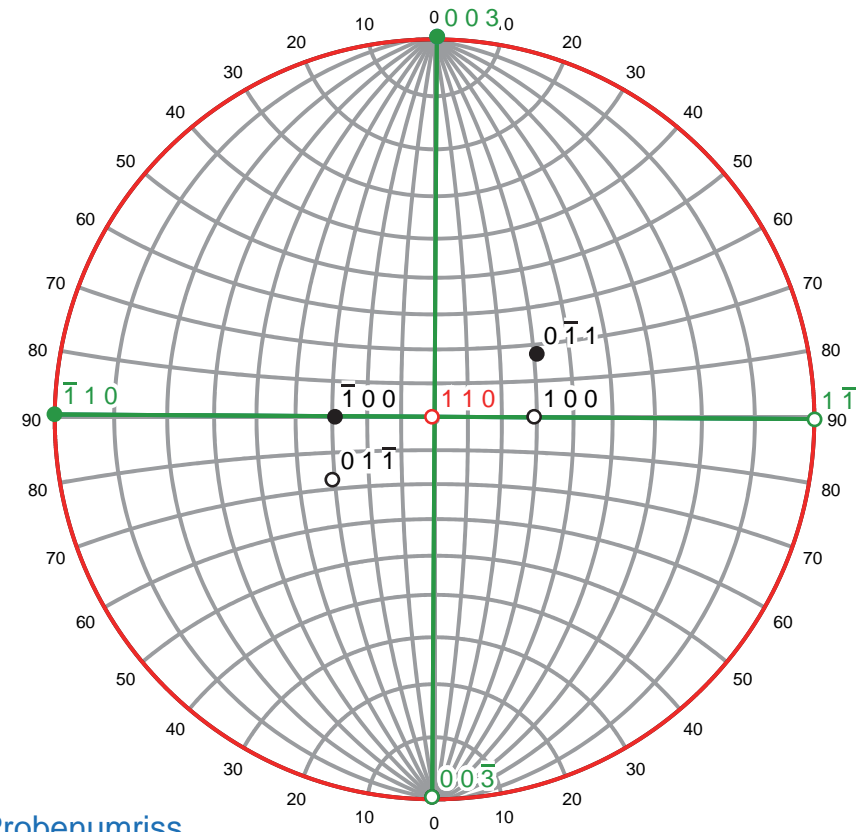
Drehung um Y-Achse

Drehung um Z-Achse

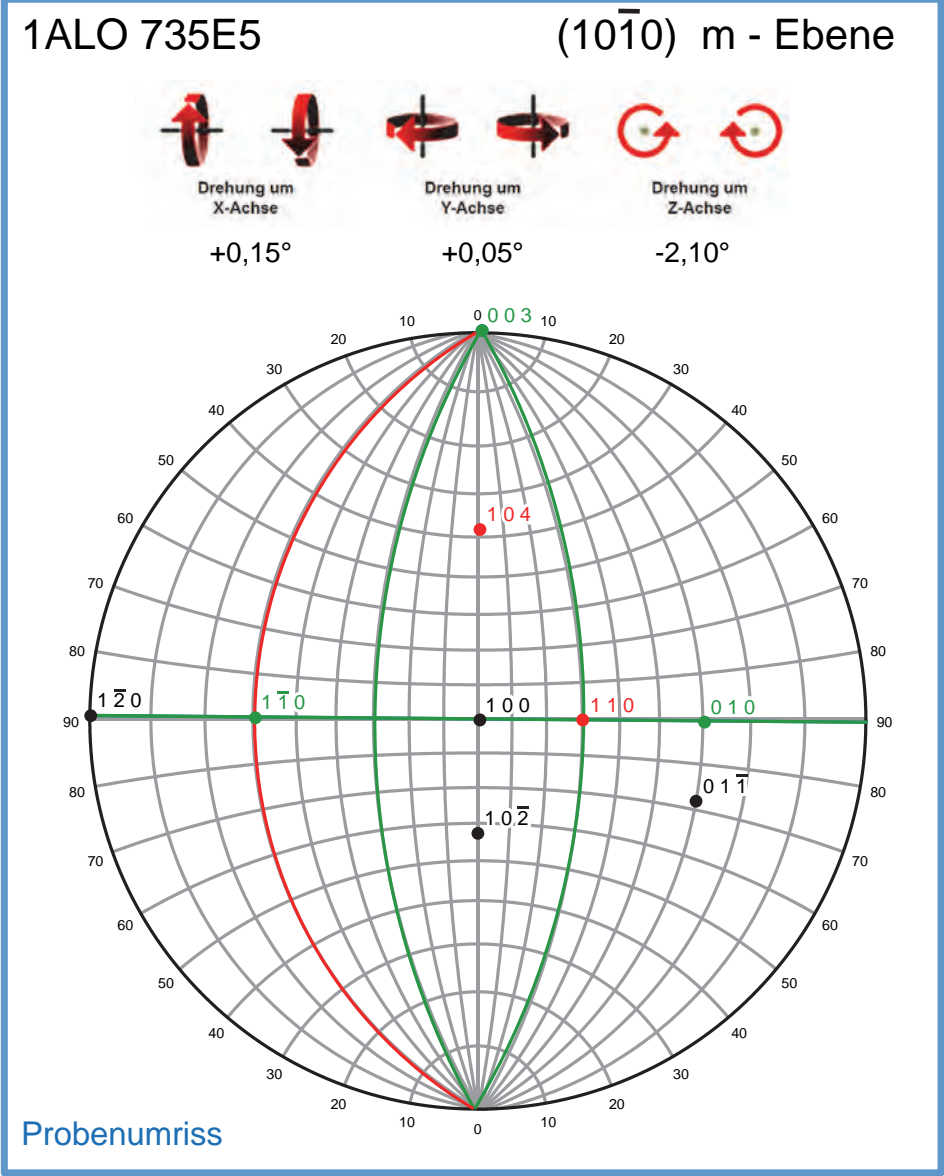
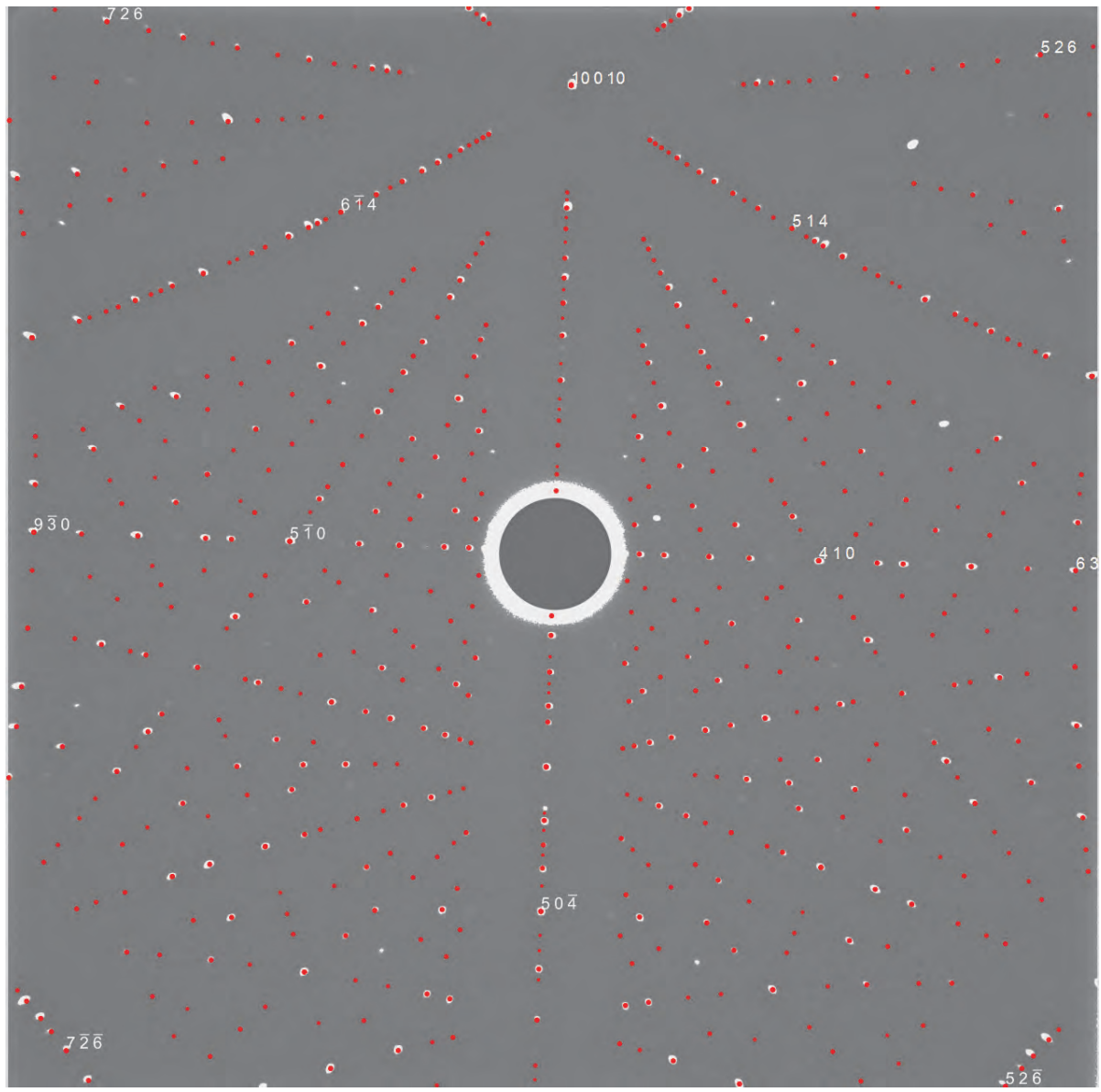
+0,20°

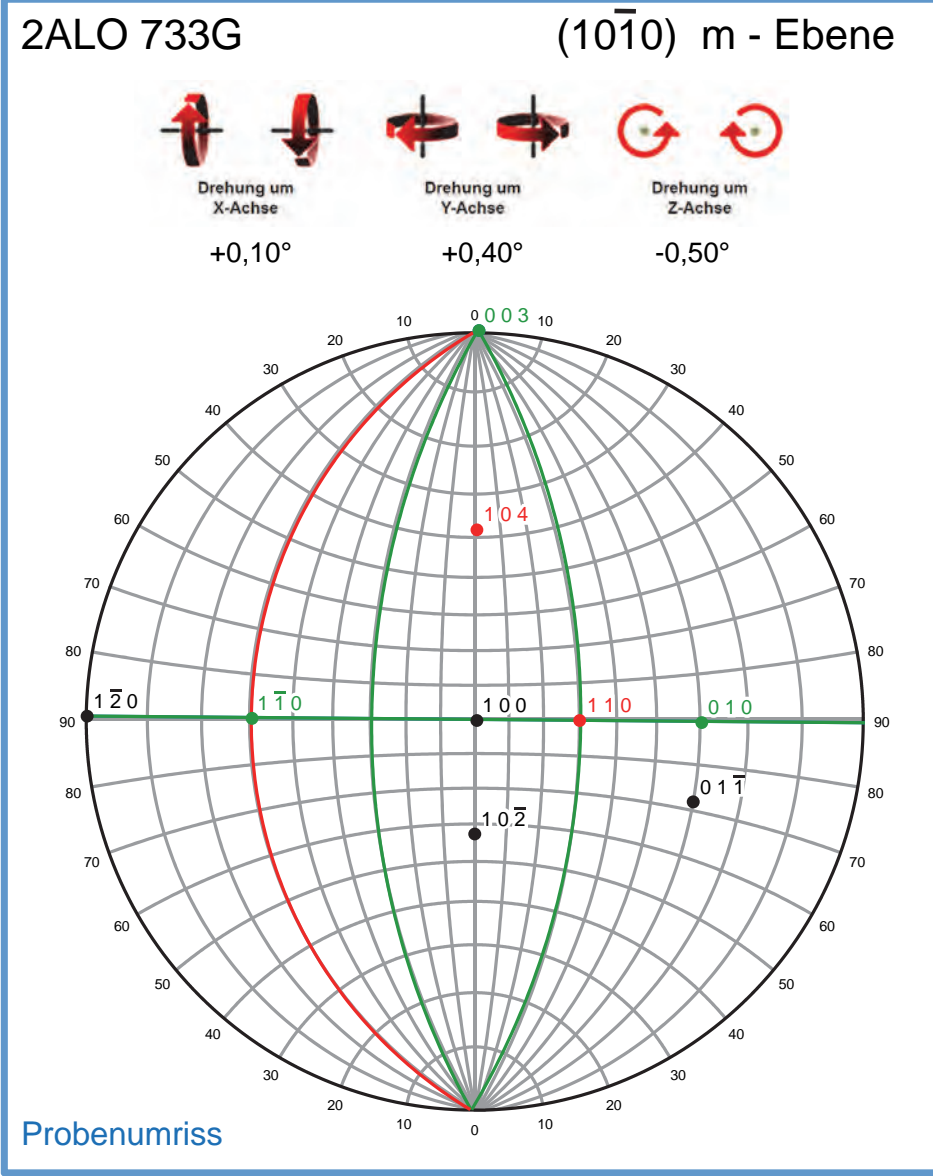
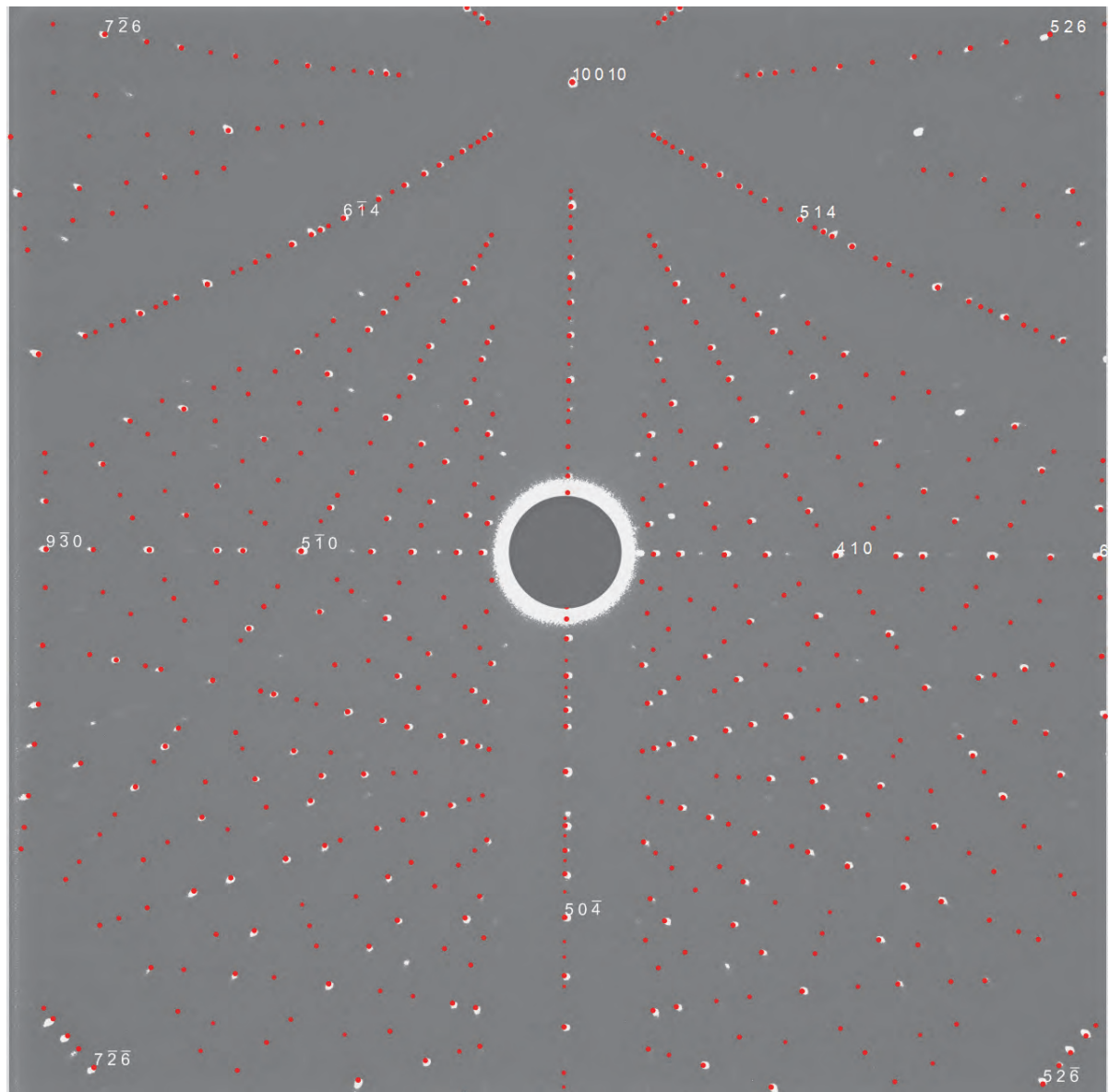
+0,40°

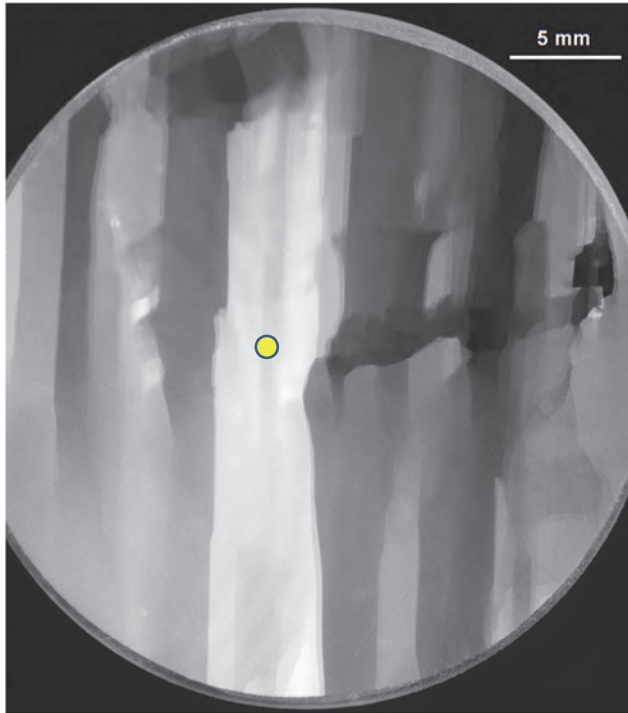
-0,35°



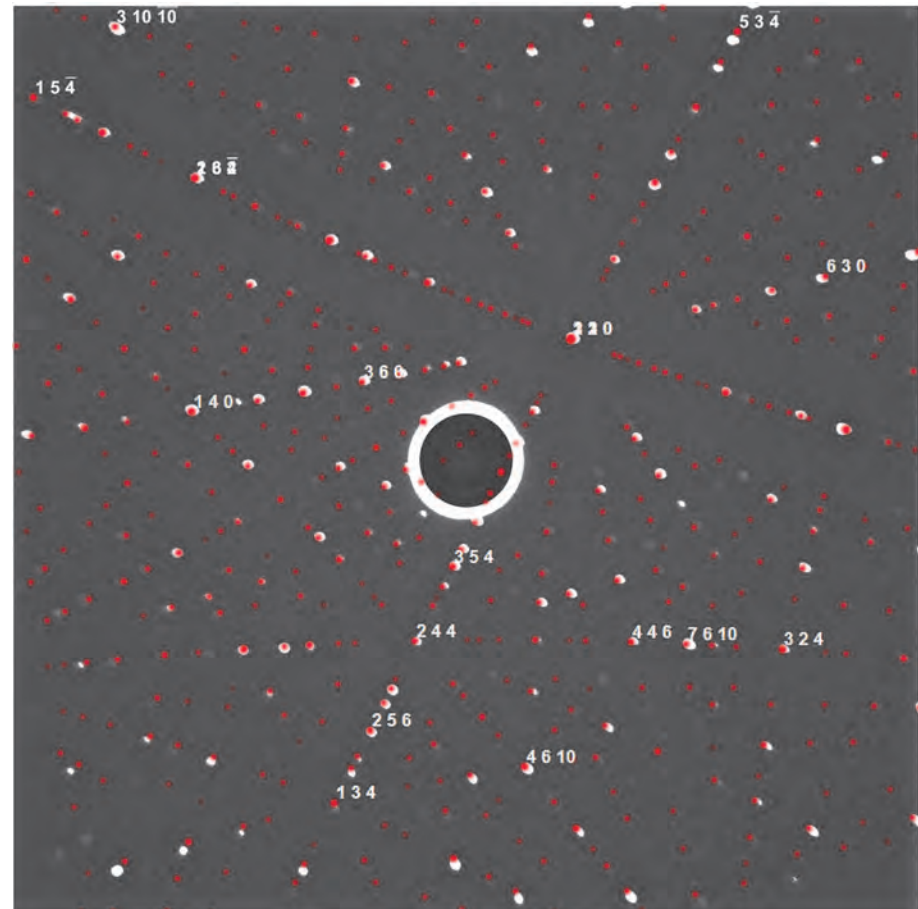
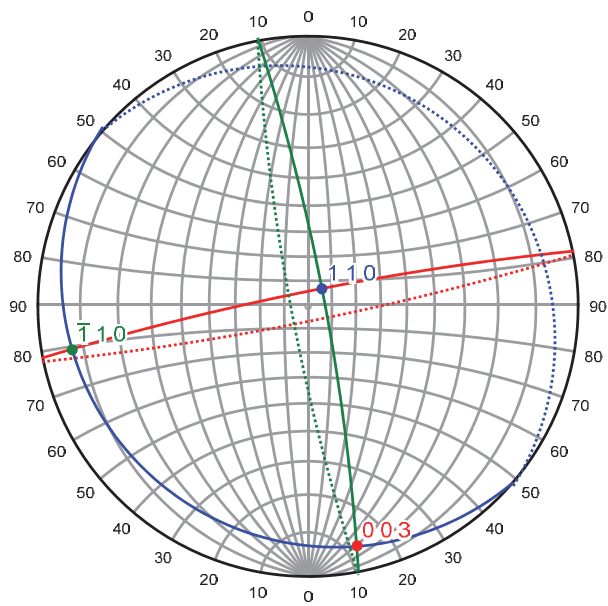
Probenumriss

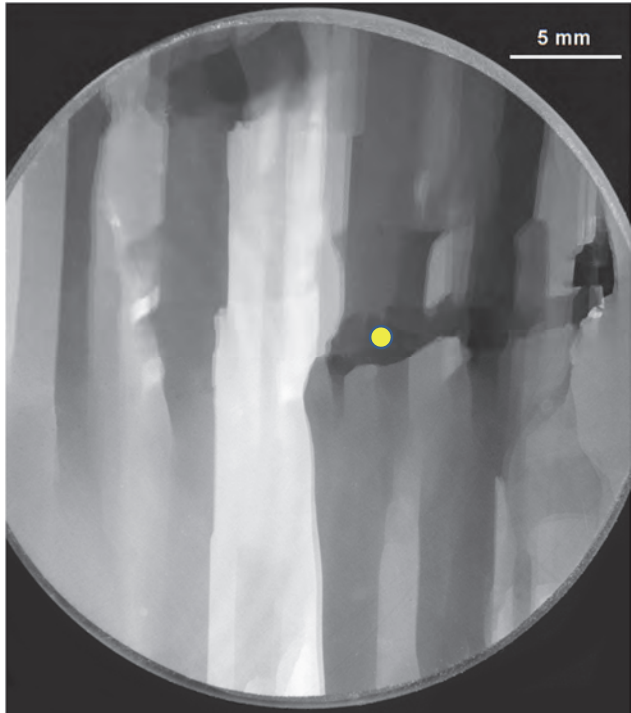




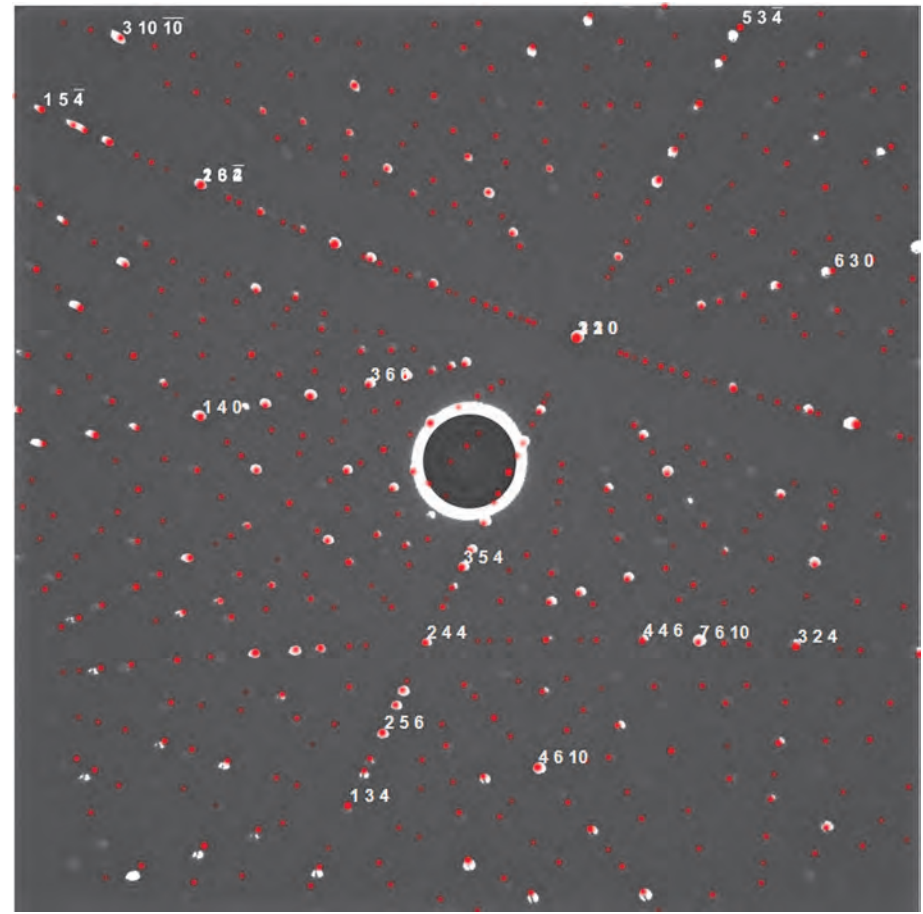
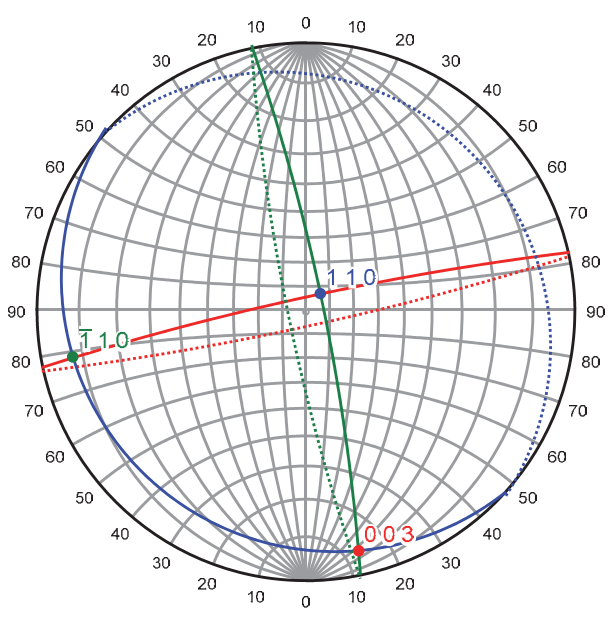


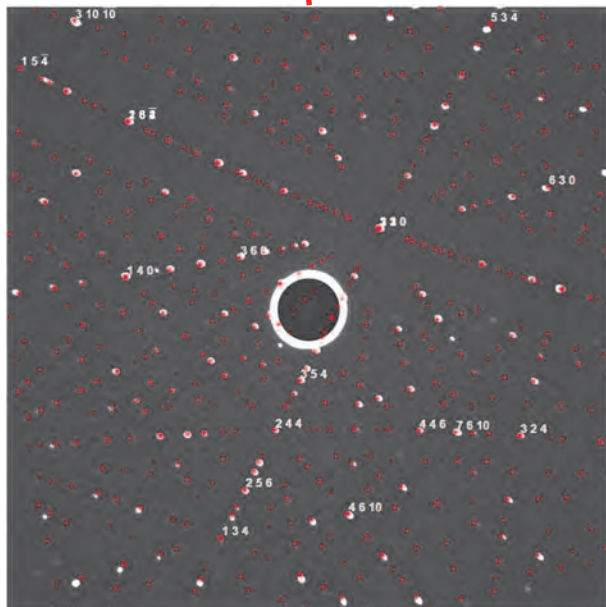
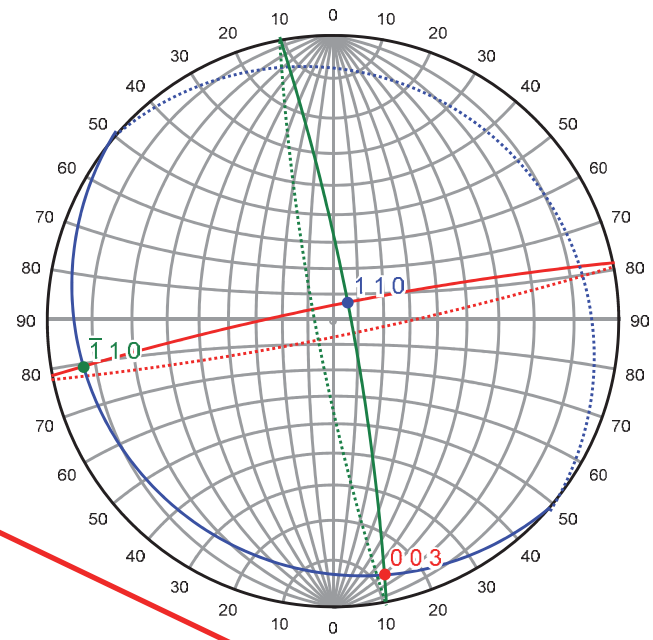
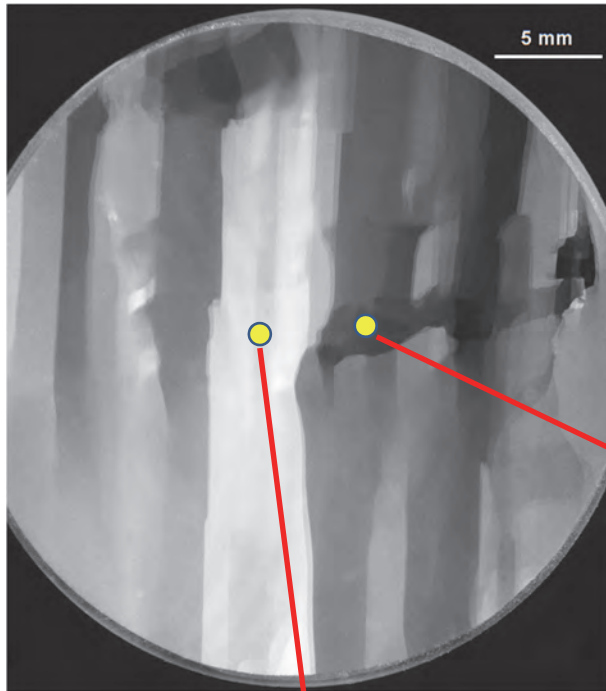
Neigung der (11.0) Ebene zur Oberfläche





Neigung der (11.0) Ebene zur Oberfläche





+0,1°



+0,4°



+0,9°

